WHAT IS CLAIMED IS:

- 1. A semiconductor laser device comprising:
- a heat radiating block;

one or more first semiconductor laser element(s)

5 arranged on said heat radiating block in a manner where one electrode is in contact therewith; and

one or more second semiconductor laser element(s) arranged on said heat radiating block in an electrically insulated manner via a dielectric layer.

2. The semiconductor laser device as set forth in Claim 1, wherein

said first and second semiconductor laser elements are both integrated into one chip, and one electrode of the first semiconductor laser element is in contact with said block, and the second semiconductor laser element is provided on said dielectric layer.

3. The semiconductor laser device as set forth in Claim 1, wherein

said heat radiating block is an electrical conductor or a semiconductor.

4. The semiconductor laser device as set forth in Claim 2, wherein

said heat radiating block is an electrical conductor or a semiconductor.

- 5. The semiconductor laser device as set forth in Claim 1, comprising:
 - a light output monitoring photodiode built onto said heat radiating block.

- 6. The semiconductor laser device as set forth in Claim 2, comprising:
- a light output monitoring photodiode built onto said heat radiating block.
- 7. The semiconductor laser device as set forth in Claim 3, comprising:
 - a light output monitoring photodiode built onto said heat radiating block.
- 8. The semiconductor laser device as set forth in
 10 Claim 1, wherein

said dielectric layer is formed of one selected from a group consisting of silicon oxide, silicon nitride, titanium oxide, aluminum oxide, and aluminum nitride.

The semiconductor laser device as set forth in
 Claim 2, wherein

said dielectric layer is formed of one selected from a group consisting of silicon oxide, silicon nitride, titanium oxide, aluminum oxide, and aluminum nitride.

10. The semiconductor laser device as set forth in 20 Claim 3, wherein

said dielectric layer is formed of one selected from a group consisting of silicon oxide, silicon nitride, titanium oxide, aluminum oxide, and aluminum nitride.

11. The semiconductor laser device as set forth in 25 Claim 1, wherein

said first semiconductor laser element is greater in heat generation during driving or smaller in heat radiation from an element exposed surface than said second

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semiconductor laser element.

12. The semiconductor laser device as set forth in Claim 2, wherein

said first semiconductor laser element is greater in

heat generation during driving or smaller in heat radiation
from an element exposed surface than said second
semiconductor laser element.

- 13. The semiconductor laser device as set forth in Claim 3, wherein
- said first semiconductor laser element is greater in heat generation during driving or smaller in heat radiation from an element exposed surface than said second semiconductor laser element.
- 14. The semiconductor laser device as set forth in 15 Claim 1, wherein

said first semiconductor laser element is a semiconductor laser to emit a laser beam with a 650nm-band wavelength, and said second semiconductor laser element is a semiconductor laser to emit a laser beam with a 780nm-band wavelength.

15. The semiconductor laser device as set forth in Claim 2, wherein

said first semiconductor laser element is a semiconductor laser to emit a laser beam with a 650nm-band wavelength, and said second semiconductor laser element is a semiconductor laser to emit a laser beam with a 780nm-band wavelength.

16. The semiconductor laser device as set forth in

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Claim 3, wherein

said first semiconductor laser element is a semiconductor laser to emit a laser beam with a 650nm-band wavelength, and said second semiconductor laser element is a semiconductor laser to emit a laser beam with a 780nm-band wavelength.